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1/8/04

OPTICAL SYSTEM

Abstract

An optical system, for example a projection exposure apparatus for microlithography, has at least one optical element with an optical surface. A correction radiation device is provided that includes at least one correction radiation source for emitting correction radiation. A scanning device has at least one scanning mirror that is irradiated by the correction radiation and driven in such a way that a defined portion of the optical surface of the optical element is scanned with the correction radiation. This results in a correction of imaging characteristics of the optical element by means of heat which is supplied to the optical element by the correction radiation.